JUN 1 2 2002

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

RADEND Te application of: Shrinivasan et al.

Attorney Docket No.:

NOVLP029/NVLS-000495

Application No.: 10/067,520

Examiner: Not yet assigned

Filed: February 5, 2002

Group: 2811

Title: APPARATUS AND METHODS FOR

PROCESSING SEMICONDUCTOR

SUBSTRATES USING SUPERCRITICAL

FLUIDS

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Pastal Service as First Class Mail to: Commissioner for Patents, Washington, DC 20231 on May 31, 2002.

Signed:

Tara Hayden

INFORMATION DISCLOSURE STATEMENT 37 CFR §§1.56 AND 1.97(b)

Commissioner for Patents Washington, DC 20231

Dear Sir:

The references listed in the attached PTO Form 1449, copies of which are attached, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prices.

This Information Disclosure Statement is: (i) filed within three (3) mond, of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure

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Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. NVLSP029).

Respectfully submitted,

BEYER WEAKER, & THOMAS, LLP

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\	Form 449 (Modified)	Atty Docket No.	Application No.:			
CATENT &	TO AD CHART	NOVLP029/000495	10/067,520			
10	Information Disclosure	Applicant:				
	Statement By Applicant	Shrinivasan et al.				
		Filing Date	Group			
	(Use Several Sheets if Necessary)	February 5, 2002	2811			

U.S. Patent Documents

Examiner						Sub-	Filing Date
Initial	No.	Patent No.	Date	Patentee	Class	class	Date
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Foreign Patent or Published Foreign Patent Application

Examiner		Document	Publication			Sub-	Trans	Translation	
Initial	No.	No.	Date	Patent Office	Class	class	Yes	No	
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Other Documents

Examiner						
Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication				
	A	Biberger et al., "High Pressure Processing Chamber for Semiconductor Substrate", Pub. No. US 2002/0046707 A1, Pub. Date: April 25, 2002, Ap No.: 09/912,844, Filed: July 24, 2001, pp. 1-19.				
Examiner		Date Considered				

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.